# Nanotechnology - introduction 

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## Welcome!

What is Nanotechnology?




$$
\begin{aligned}
& \mathrm{SSA}=\frac{\mathrm{A}}{\mathrm{~V} \rho} \\
& {[\mathrm{SSA}]=\frac{\mathrm{m}^{2}}{\mathrm{~g}}}
\end{aligned}
$$

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[\mathrm{SSA}]=\frac{\mathrm{m}^{2}}{\mathrm{~g}}
$$




Bandgap

$$
\begin{equation*}
\mathrm{E}_{\mathrm{nano}}=\mathrm{E}_{\mathrm{g}, \mathrm{bulk}}+\frac{\mathrm{h}^{2} \pi^{2}}{2 \mathrm{mr}_{\text {nano }}^{2}} \tag{1}
\end{equation*}
$$



Why?

## Bandgap

$$
\begin{equation*}
\mathrm{E}_{\text {nano }}=\mathrm{E}_{\mathrm{g}, \text { bulk }}+\frac{\mathrm{h}^{2} \pi^{2}}{2 \mathrm{mr}_{\text {nano }}^{2}} \tag{1}
\end{equation*}
$$

Melting temperature

Why?

Bandgap

$$
\begin{equation*}
\mathrm{E}_{\text {nano }}=\mathrm{E}_{\mathrm{g}, \mathrm{bulk}}+\frac{\mathrm{h}^{2} \pi^{2}}{2 \mathrm{mr}_{\text {nano }}^{2}} \tag{1}
\end{equation*}
$$

Melting temperature

Interactions with environment
Cassie-Baxter

## Top-Down

VS.
Bottom-Up

Nucleation and growth


[^0]Nucleation and growth
Scanning Probe Microscopy (SPM)


## Production?

Nucleation and growth SPM
Molecular Beam Epitaxy (MBE)


Nucleation and growth SPM

MBE
Polymer origami


Rothemund, Nature, 2006

## Production?

Nucleation and growth SPM
MBE
Polymer origami Lithography
Dip-pen, Soft lithography...


Top-down
Lithograhpy
Photolithography, EBL, SCIL, NIL...


Top-down
Lithograhpy
Photolithography, EBL, SCIL, NIL...
Forces
Shear, impact

Top-down
Lithograhpy
Photolithography, EBL,
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Forces
Shear, impact


Top-down
Lithograhpy
Photolithography, EBL, SCIL, NIL...
Forces
Shear, impact
Partial dissolution
Acids, bases


## Characterization

## Statistical

- X-Ray Scattering (WAXS/SAXS)
- Neutron Scattering
- Nuclear Magnetic Resonance (NMR)


$$
\mathrm{d}=\frac{\lambda}{2 \mathrm{NA}}, \mathrm{~d}>0.25 \mu \mathrm{~m}
$$

STED, PALM, STORM, SIM...




Increasing Z



This is an actual picture of a molecule
Image credit: IBM Research - Zurich
$1-3 \mathrm{D} \in\{1,100\} \mathrm{nm}$

## $1-3 \mathrm{D} \in\{1,100\} \mathrm{nm}$

 novel properties
## summary

$1-3 \mathrm{D} \in\{1,100\} \mathrm{nm}$ novel properties
Build from ground up
Produce from larger whole
$1-3 \mathrm{D} \in\{1,100\} \mathrm{nm}$ novel properties
Build from ground up
Produce from larger whole
Demanding characterization


[^0]:    Sulalit Bandyopadhyay, Mat. Today, 2017

